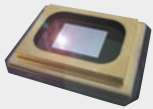


MASKLESS PHOTOLITHOGRAPHY SYSTEM

D-light **DL-1000**

Utilizing Digital Micromirror Device(DMD)Technology



Utilizing Digital Micromirror Device (DMD) Technology for pattern projection with 1 μ m resolution.

Fast Projection
>200mm²/min

by scanning method

Unique Auto Focus Technology

Thin and transparent Substrate

Thick Photoresist

Applicable for t >100 μ m

DXF, GDS II Data Format

Data Conversion Software

3D Process on Photo-Resist

Gray Scale Exposure

TTL Auto Alignment

Accurate Overlay

Smooth Curvature Projection

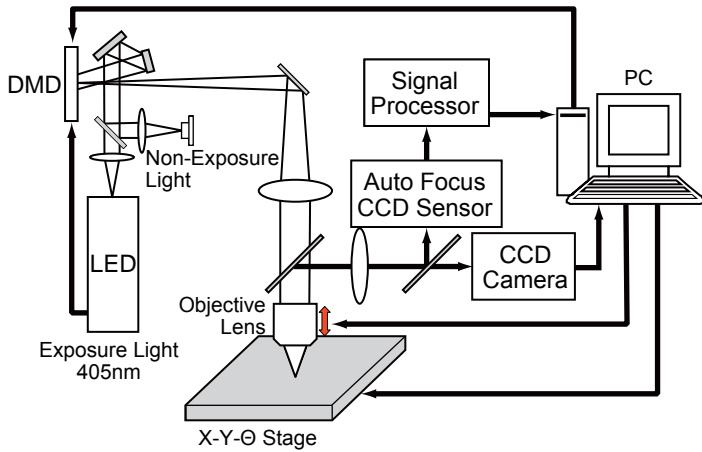
High Resolution Projection Mode

Efficient Optimization

Test Exposure Mode

Leading Edge Direct Lithography by Digital Technologies

System Layout



Specifications

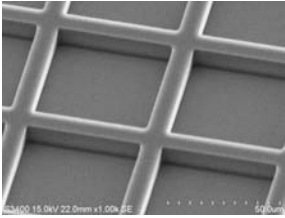
Illumination	LED
Wave Length (Main)	405nm
Exposure Power	1W/cm ² or more
Resolution	1μm (Standard)
Work Size	□100mm (Standard), Up to □500mm (as Option)
Over layer Accuracy	±1μm or better
Positioning Accuracy	±0.1μm (measured by equipped scale)
Exposure Uniformity	±5% or better
Max Process Speed	50mm ² /min or faster (※1)
Gray Scale Exposure	Max 256 gradation (※2)
Dimension (Main Unit)	※855mm×※820mm×H1500mm
Weight	approx 520kg

※ 1 Scanning Method can perform up to 200mm²/min.

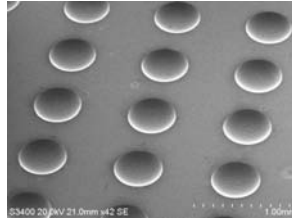
※ 2 For the model which is equipped Gray Scale Data Software

Application Samples

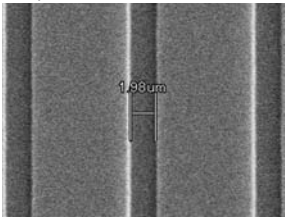
■ Grating



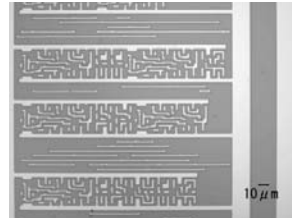
■ Lens Shape



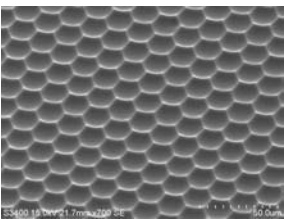
■ 2μm Line



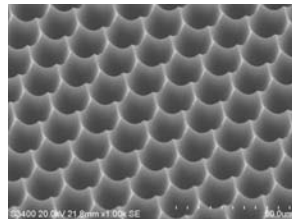
■ 2D Patterns



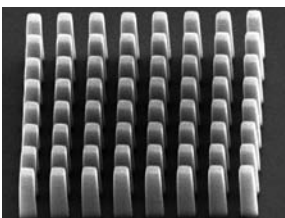
■ Micro Lens Array



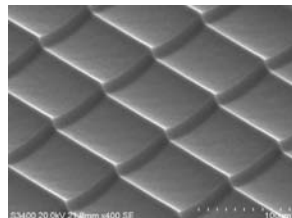
■ HCP Structure



■ Thick Photo Resist

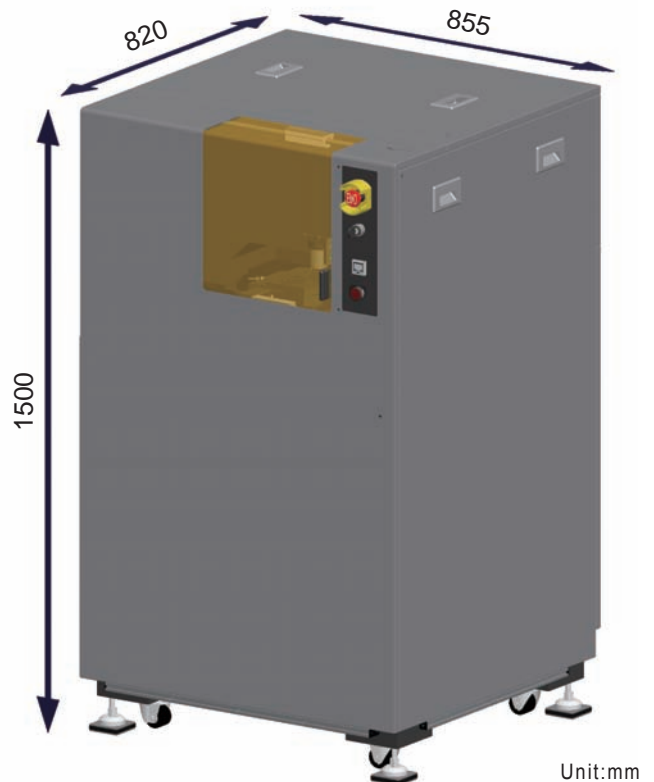


■ Tile Shape



Utilities, Installation Environment

Power	AC100V 50/60Hz 15A
Temperature	22 ~ 25°C ±1°C
Humidity	30 ~ 60% (No Condensation)
Clean Room	Class 1000 or better



Unit:mm

※This Catalog has been issued as of May 2012. The contents, descriptions, specification, or dimensions may be changed without notice.
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